

**REQUEST FOR RECONSIDERATION**  
**Appln. No. 09/834,501**

**PATENT APPLICATION**

IN THE CLAIMS:

The following listing of claims will replace all prior versions, and listings of claims in the application:

Listing of Claims:

Claims 1-12. (Canceled)

13. (Previously Presented) The processing system of claim 20, wherein each of the plural article supports is sufficiently wide to support one of the two semiconductor articles on its upper surface, wherein each of the article supports is substantially wider than its respective stem, and wherein the pumping port is located at least partially beneath each of the plural article supports.

14. (Previously Presented) The processing system of claim 20, wherein each of the plural article supports is supplied, via its respective stem, with DC potential, helium gas, and coolant.

15. (Previously Presented) The processing system of claim 20, wherein each of the plural stems comprises bellows permitting linear motion, along a longitudinal axis of that stem, of the respective article support with respect to the bottom wall of the chamber body.

16. (Previously Presented) The processing system of claim

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21, wherein the pumping port is located at least partially beneath each of the plural article supports.

Claims 17-19. (*Canceled*)

20. (*Previously Presented*) A processing system for simultaneously processing plural semiconductor articles under substantially identical process conditions, the processing system comprising:

a chamber body having a bottom wall with a pumping port formed in the bottom wall;

a vacuum pump in fluid communication with the pump port;

plural article supports disposed inside the chamber body, each of the plural article support comprising: an upper surface, and a lower surface facing the bottom wall;

plural stems, each supporting a respective one of the plural article supports, each of the plural stems extending from the bottom wall to the lower surface of its respective article support; and

a partition extending partially toward the bottom wall from a top wall of the chamber body downward between the plural article supports;

wherein each of the plural article supports is sufficiently wide to support one of the plural semiconductor articles on its

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upper surface, and wherein each of the article supports is substantially wider than its respective stem.

21. *(Previously Presented)* A processing system for simultaneously processing plural semiconductor articles under substantially identical process conditions, the processing system comprising:

a chamber body having a bottom wall with a pumping port formed in the bottom wall;

a vacuum pump in fluid communication with the pump port;

plural article supports disposed inside the chamber body, each of the plural article supports being sufficiently wide to support one of the plural semiconductor articles thereon; and

a partition extending partially toward the bottom wall from a top wall of the chamber body downward between the plural article supports.

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